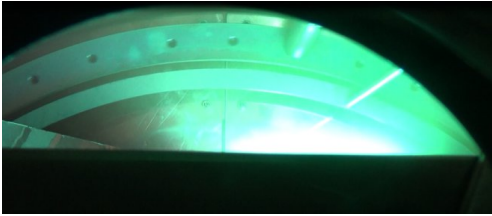


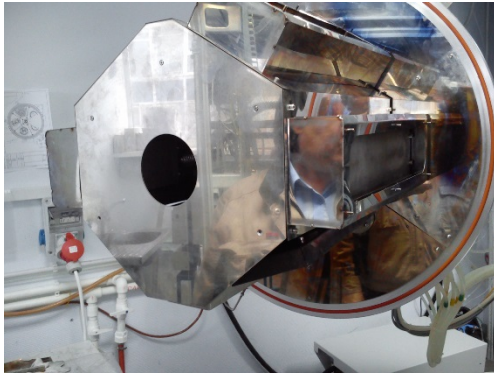
# Magnetron L400



The extended magnetron L400 is designed for applying thin films of various materials to a substrate in a vacuum. The target is rectangular 400 mm.

In the direct current mode, it is possible to deposit metals, alloys (including resistive ones) while maintaining the stoichiometric composition.

When using a pulsed medium-frequency power supply, it is possible to deposit semiconductors and dielectrics in a reactive mode from metal targets.



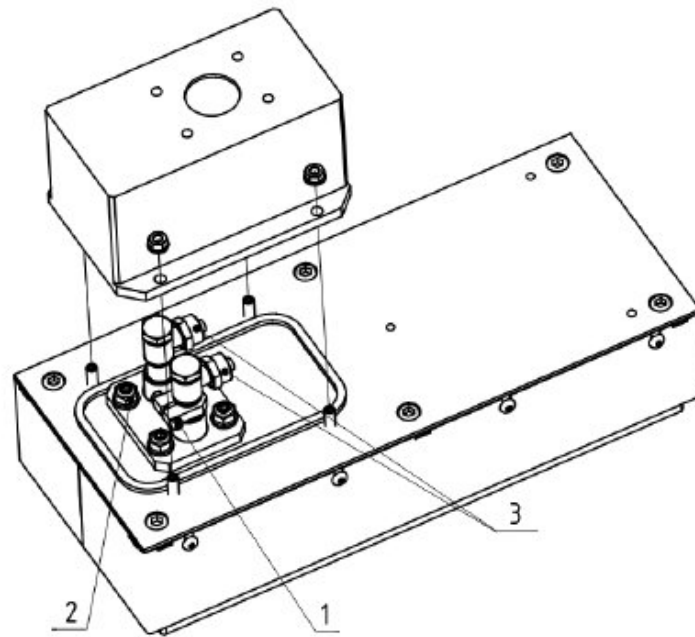
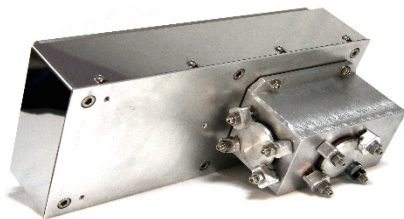
Параметр	Значение
Maximum power	12 000 W
Maximum current	20 A
Target size (length x width)	400 x 94 mm
<i>Height 6 mm (for magnetic, 10 for non-magnetic)</i>	
Weight	15 kg (no more than)
Coolant consumption	2 l/min at 3 kW, 4 l/min - 7 kW, 5 l/min-12 kW

The design allows for various combinations of magnetron placement in the chamber.



Magnetron M-400

# Magnetron L400 (basic dimensions)



- 1 – earth contact stud
- 2 – power connection terminal («-»)
- 3 – fittings for coolant connection

